

PROCESSING SOLUTION FEEDING METHOD AND DEVICE

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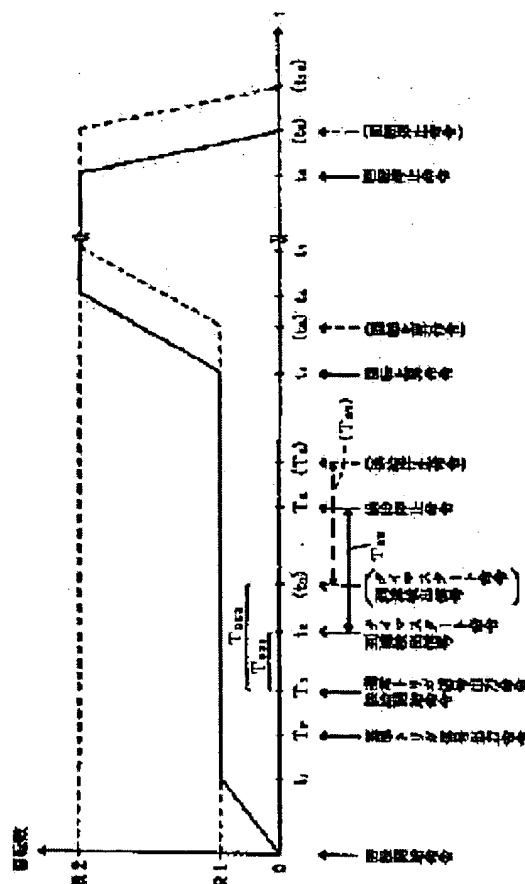
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Abstract of JP9270373

PROBLEM TO BE SOLVED: To execute a feed start command and execute the later commands according to the arrival of a processing solution at a substrate.

SOLUTION: A substrate is spin-driven to reach a revolution per minute R1 at the time t1 by the spin starting command so that a feed starting command may be executed at a time Ts to start feeding a photoresist solution at a specific flow rate. Next, at the time point of t2 detecting the arrival of the photoresist solution at the surface of the substrate, the timer starting command counting the elapse time is executed so as to execute the feed stopping command at the time point of arriving at the feed time Tsu (time TE) to stop feeding the photoresist solution. Finally, at the time t4, by executing a spin rising command, the revolution per minutes can be accelerated so that the substrate may arrive at the revolution per minutes R2 at the time t6 to execute the spin stopping command at the time t8 further to finish the coating step at the time t9.



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